# GEANT4 Works
# Chamber Profile adjusting

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# Chamber profile

## K stop position distribution

10001(10.00%) 8555(8.55%)
6070(6.07%) 5839(5.84%)



hc4wy

Y (cm)

X (cm)



eff

100000(100%)

10001(10.00%) 8555(8.55%)
6070(6.07%) 5839(5.84%)

Y (cm)

Z (cm)
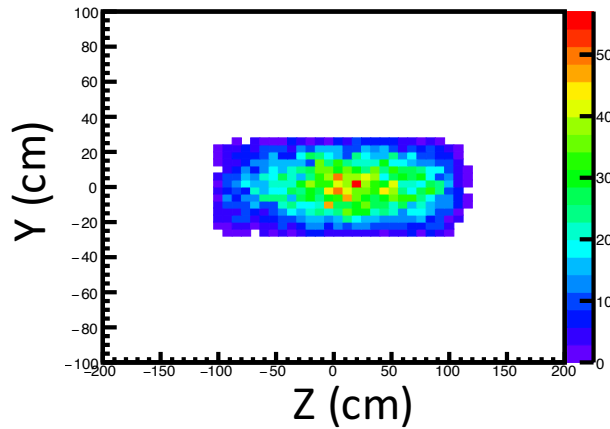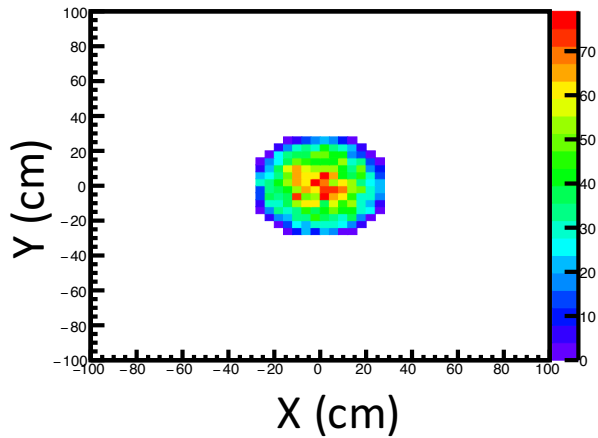
RandomGaus:

σx=1.0 cm
σy=1.0 cm
σz=3.0 cm

σx=1.8 cm
σy=1.8 cm
σz=7.5 cm

## Magnetic Field Intensity Dependence



hc2z

+1.0%
+0.5%
- 0.5%
- 1.0%

C2Z (cm)

targE



hc3r

C3R (cm)

angleAcc



hc3y

C4R (cm)

KstopPos primPhi
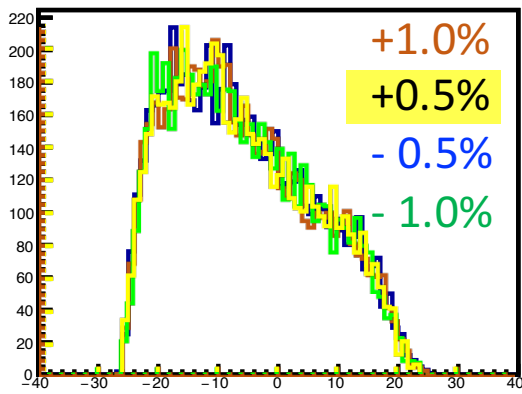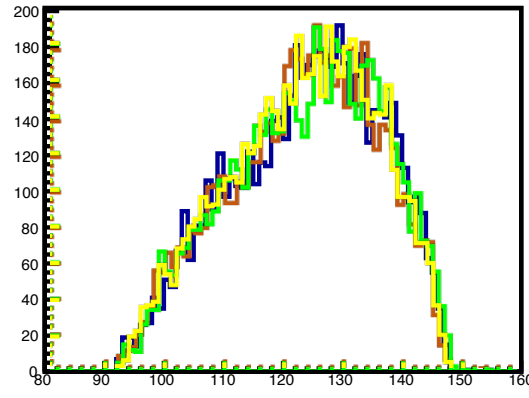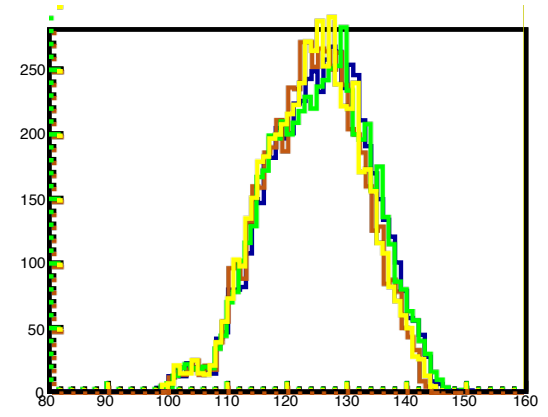
# Summary

- K stop distribution and Magnetic field intensity were adjusted so that the Chamber profiles match in exp. and MC simu.

- E36 G4 MC environment made by me was copied into KEKCC Environment of Kimura and Kobayashi. They were demonstrated to work at Chiba Univ.